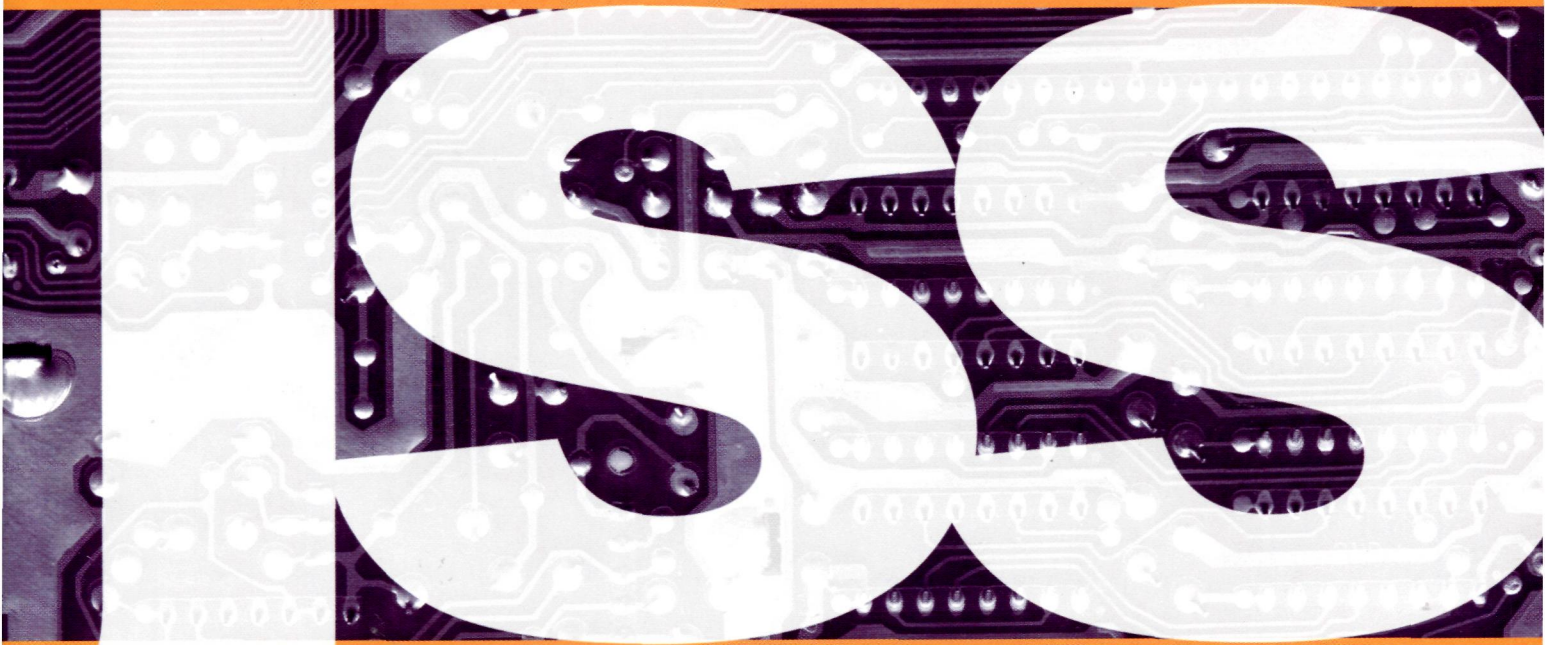
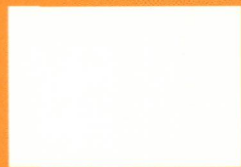


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Focus Issue on Semiconductor Surface Cleaning and Conditioning



Table of Contents

Commentary

Preface to the Focus Issue on Semiconductor Surface Cleaning and Conditioning

Jerzy Ruzyllo, Takeshi Hattori Y1

Dielectric Science and Materials

Comparative Surface Study on Silicon Dioxide Film Covered with Alcohols

Nobuyoshi Sato, Yukihiro Shimogaki N3001

Cleaning Process Applicable to Silicon Carbide Chemical Vapor Deposition Reactor

Hitoshi Habuka, Yusuke Fukumoto, Kosuke Mizuno, Yuuki Ishida, Toshiyuki Ohno N3006

Nanoparticle Removal with Megasonics: A Review

S. Brems, M. Hauptmann, E. Camerotto, A. Pacco, T.-G. Kim, X. Xu, K. Wostyn, P. Mertens, S. De Gendt N3010

Study of InP Surfaces after Wet Chemical Treatments

D. Cuypers, D. H. van Dorp, M. Tallarida, S. Brizzi, T. Conard, L. N. J. Rodriguez, M. Mees, S. Arnauts, D. Schmeisser, C. Adelman, S. De Gendt N3016

Post Cu CMP Cleaning of Polyurethane Pad Debris

Wei-Tsu Tseng, Elliott Rill, Benjamin Backes, Mark Chace, Yiping Yao, Patrick DeHaven, Adam Ticknor, Vamsi Devarapalli, Mahmoud Khojasteh, David Steber, Laertis Economikos, Connie Truong, Christopher Majors N3023

Importance of Bubble Size Control in Ultrasonic Surface Cleaning by Pulsed High-Frequency Sound Fields

M. Hauptmann, H. Struyf, S. De Gendt, C. Glorieux, S. Brems N3032

Dependency of the Underlying Surface Condition on Dielectric Film Removal at Wafer Edge

Nobuyoshi Sato, Yukihiro Shimogaki N3041

Photoresist Removal-Cleaning Technology Using Cryogenic Micro-Solid Nitrogen Spray

Jun Ishimoto, U. Oh, Tomoki Koike, Naoya Ochiai N3046

Non-Aqueous Cleaning Challenges for Preventing Damage to Fragile Nano-Structures: A Review

Takeshi Hattori N3054

Assessment of the Progress in Gas-Phase Processing of Silicon Surfaces

Jerzy Ruzyllo N3060

Etching of III-V Materials Determined by ICP-MS with Sub-Nanometer Precision

J. Rip, D. Cuypers, S. Arnauts, F. Holsteyns, D. H. van Dorp, S. De Gendt N3064

Particle Cleaning Technologies to Meet Advanced Semiconductor Device Process Requirements

Harald F. Okorn-Schmidt, Frank Holsteyns, Alexander Lippert, David Mui, Mark Kawaguchi, Christiane Lechner, Philipp E. Frommhold, Till Nowak, Fabian Reuter, Miquel Banchs Piqué, Carlos Cairós, Robert Mettin N3069

Role of Ambient Composition on the Formation and Shape of Watermarks on a Bare Silicon Substrate

A. H. Tamaddon, P. W. Mertens, J. Vermant, G. Vereecke, F. Holsteyns, M. Heyns, S. De Gendt N3081

Characterization of Cleanroom Dry Wipers for Trace Metal Contaminations

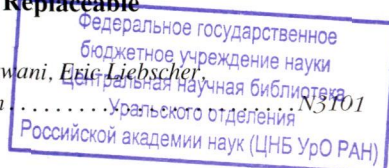
Shi Liu, Bin Liu N3087

Partial Wetting of Aqueous Solutions on High Aspect Ratio Nanopillars with Hydrophilic Surface Finish

G. Vereecke, XiuMei Xu, W. K. Tsai, Hui Yang, S. Armini, T. Delande, G. Doumen, F. Kentie, Xiaoping Shi, I. Simms, K. Nafus, F. Holsteyns, H. Struyf, S. De Gendt N3095

Analysis of Sonoluminescence Signal from Megasonic Irradiated Gas-Containing Aqueous Solutions Using Replaceable Single-Band Filters

Zhenxing Han, Manish Keswani, Eric Liebscher, Mark Beck, Srini Raghavan N3101



Study of Wet Surface Activation Routes to Enable the Deposition of Monomolecular Organic Thin Films on k 2.0 Porous Dielectrics

S. Armini, J. Loyo Prado, M. Krishtab, T. Conard, J. Meersschaut, Q. T. Le, P. Verdonck, M. R. BaklanovN3106

Numerical Analysis of Single Bubble Behavior in a Megasonic Field by Non-Spherical Eulerian Simulation

Naoya Ochiai, Jun IshimotoN3112

Thermodynamics and Kinetics of Liquid Removal from Nano-Features during Single-Wafer Spin Cleaning

Jing Liu, Junxiao Wu, Xiaoyi He, Madhukar Rao, Charles W. Monroe N3118

